

AMENDMENT UNDER 37 C.F.R. §1.116
U.S. Appln. No. 09/295,329

D/ (A) a polymer which has alicyclic hydrocarbon skeletons and decomposes by the action of an acid to thereby become alkali-soluble,

(B) a compound which generates an acid upon irradiation with actinic rays,

(C) a nitrogen-containing basic compound, and

(D) at least one fluorine-containing surfactant.

D2 Claim 2 (twice amended). A positive photosensitive resin composition comprising:

(A) a polymer which has bridged alicyclic hydrocarbon skeletons and decomposes by the action of an acid to thereby become alkali-soluble,

(B) a compound which generates an acid upon irradiation with actinic rays,

(C) a nitrogen-containing basic compound,

(D) at least a fluorine-containing surfactant, and

(E) a solvent;

wherein the ratio of (B) to (C) by weight is from 5 to 300 and the ratio of (A) to (D) by weight is from 500 to 20,000.

D3 Claim 9 (twice amended). A positive photosensitive resin composition comprising:

AMENDMENT UNDER 37 C.F.R. §1.116
U.S. Appln. No. 09/295,329

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(A) a polymer which has alicyclic hydrocarbon skeletons and decomposes under the action of an acid to become alkali-soluble,

(B) a compound which generates an acid upon irradiation with actinic rays,

(C) a nitrogen-containing basic compound,

(D) at least a fluorine-containing surfactant, and

(E) a solvent comprising as a first solvent at least one solvent selected from the following group (a) in an amount of 60 to 90 % by weight based on the total solvent and as a second solvent a solvent selected from the following group (b) in an amount of 10 to 40 % by weight to the total solvent; the group (a) consisting of ethyl lactate, propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether propionate, methyl 3-methoxypropionate and ethyl 3-ethoxypropionate, and the group (b) consisting of solvents having a viscosity of not higher than 1 centipoise at 20°C.

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Claim 23 (twice amended). A positive photosensitive resin composition comprising:

(A) a polymer which has alicyclic hydrocarbon skeletons and decomposes by the action of an acid to thereby become alkali-soluble,

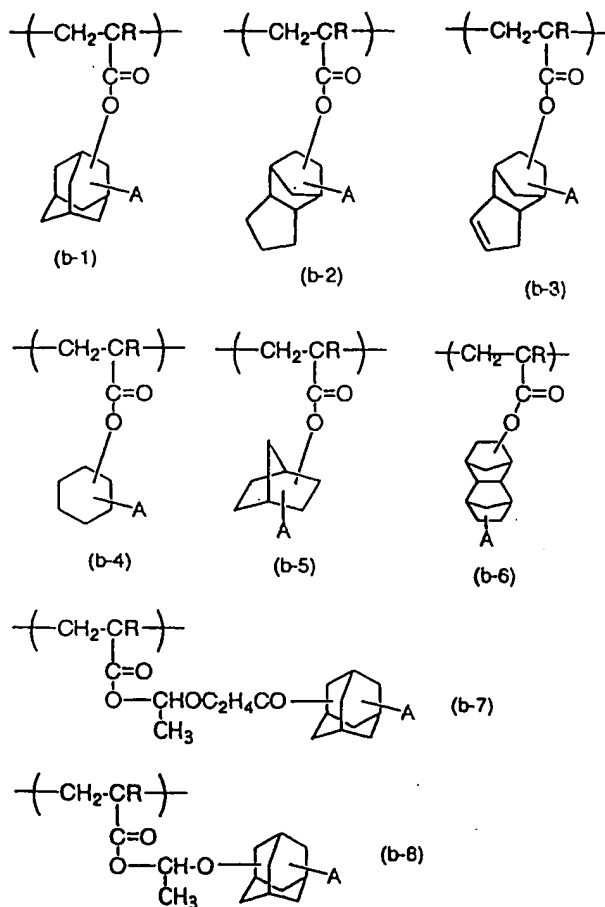
(B) a compound which generates an acid upon irradiation with actinic rays,

AMENDMENT UNDER 37 C.F.R. §1.116
U.S. Appln. No. 09/295,329

(C) a nitrogen-containing basic compound, and

(D) at least one of a fluorine-containing surfactant and a silicon-containing surfactant,

wherein said polymer which has alicyclic hydrocarbon skeletons and decomposes under the action of an acid to become alkali soluble contains a repeating unit selected from the group consisting of repeating units having the structural formulas (b-1) to (b-8):



AMENDMENT UNDER 37 C.F.R. §1.116
U.S. Appln. No. 09/295,329

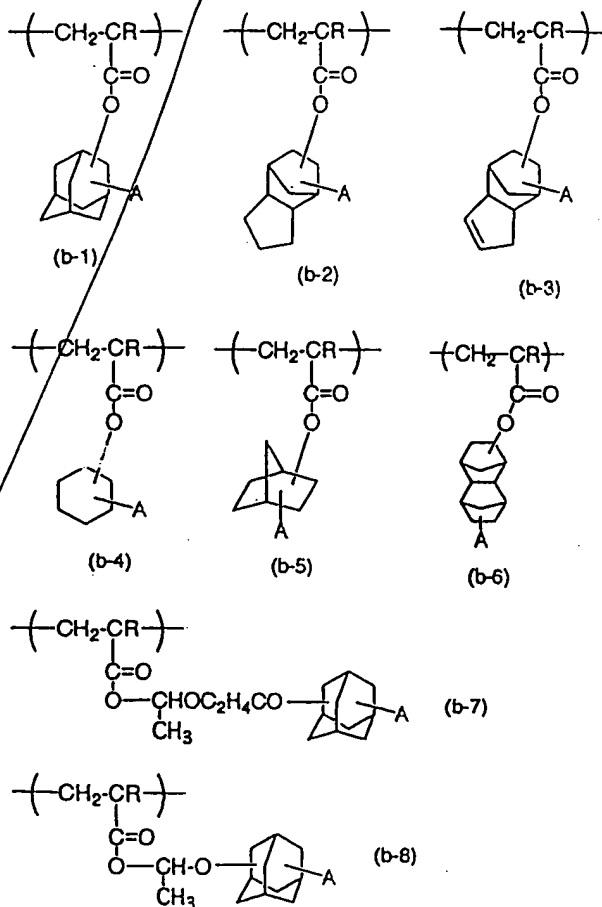
DF wherein A is selected from the group consisting of hydrogen, hydroxyl, a carboxyl group, an alkoxy carbonyl group, a substituted or unsubstituted alkyl group having from 1 to 10 carbon atoms, a substituted or unsubstituted alkoxy group having from 1 to 10 carbon atoms, and a substituted or unsubstituted alkenyl group having from 1 to 10 carbon atoms; and R is selected from the group consisting of hydrogen and a substituted or unsubstituted alkyl group having 1 to 3 carbon atoms.

Sub E1 Claim 24 (twice amended). A positive photosensitive resin composition comprising:

- (A) a polymer which has alicyclic hydrocarbon skeletons and decomposes by the action of an acid to thereby become alkali-soluble,
- (B) a compound which generates an acid upon irradiation with actinic rays,
- (C) a nitrogen-containing basic compound, and
- (D) at least one of a fluorine-containing surfactant and a silicon-containing surfactant,

wherein said polymer which has alicyclic hydrocarbon skeletons and decomposes under the action of an acid to become alkali soluble contains a repeating unit selected from the group consisting of repeating units having the structural formulas (b-1) to (b-8):

AMENDMENT UNDER 37 C.F.R. §1.116
U.S. Appln. No. 09/295,329



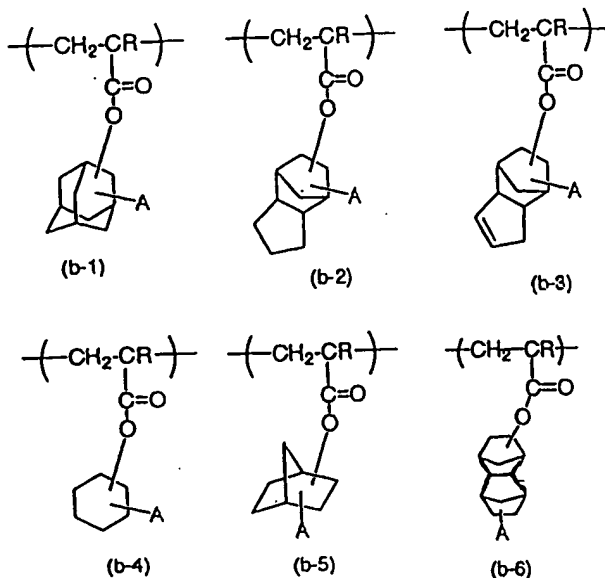
wherein A is selected from the group consisting of hydrogen, hydroxyl, a carboxyl group, an alkoxycarbonyl group, a substituted or unsubstituted alkyl group having from 1 to 10 carbon atoms, a substituted or unsubstituted alkoxy group having from 1 to 10 carbon atoms, and a substituted or unsubstituted alkenyl group having from 1 to 10 carbon atoms; and R is selected from the group consisting of hydrogen and a substituted or unsubstituted alkyl group having 1 to 3 carbon atoms.

AMENDMENT UNDER 37 C.F.R. §1.116
U.S. Appln. No. 09/295,329

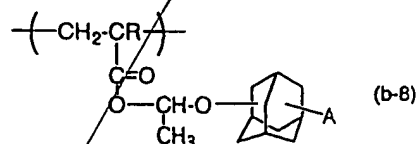
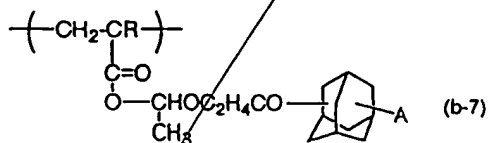
Claim 25 (twice amended). A positive photosensitive resin composition comprising:

- (A) a polymer which has alicyclic hydrocarbon skeletons and decomposes by the action of an acid to thereby become alkali-soluble,
- (B) a compound which generates an acid upon irradiation with actinic rays,
- (C) a nitrogen-containing basic compound, and
- (D) at least one of a fluorine-containing surfactant and a silicon-containing surfactant,

wherein said polymer which has alicyclic hydrocarbon skeletons and decomposes under the action of an acid to become alkali soluble contains a repeating unit selected from the group consisting of repeating units having the structural formulas (b-1) to (b-8):



AMENDMENT UNDER 37 C.F.R. §1.116
U.S. Appln. No. 09/295,329



wherein A is selected from the group consisting of hydrogen, hydroxyl, a carboxyl group, an alkoxycarbonyl group, a substituted or unsubstituted alkyl group having from 1 to 10 carbon atoms, a substituted or unsubstituted alkoxy group having from 1 to 10 carbon atoms, and a substituted or unsubstituted alkenyl group having from 1 to 10 carbon atoms; and R is selected from the group consisting of hydrogen and a substituted or unsubstituted alkyl group having 1 to 3 carbon atoms.